L Number	Hits	S arch Text	DB	Time stamp
-	91	(pattern same (h ld or h lding or support or supp rting) am mask same (alignment adj mark) same exp sur)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 16:57
-	6	(pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 16:57
-	5	(pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same (second adj alignment adj mark) same exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 16:58
-	5	((pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same (second adj alignment adj mark) same exposure)).clm	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 16:59
-	5	((pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same (second adj alignment adj mark) same exposure)).clm and beam	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 16:59
-	5	((pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same (second adj alignment adj mark) same exposure)).clm and ((electron or (charge near particle)) adj beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 17:00
-	5	((pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same (second adj alignment adj mark) same exposure)).clm and ((electron or (charge near particle)) adj beam).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 17:00
-	0	((pattern same (hold or holding or support or supporting) same mask same (first adj alignment adj mark) same (second adj alignment adj mark) same exposure)).clm. and ((electron or (charge near particle)) adj beam).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/03 17:00
-	1	((pattern same (hold or holding or support or supporting) same mask same (first adj alignm nt adj mark) same (s ond adj alignm nt adj mark) same xp sure)).clm. and ((electr n r (harge near particle)) adj beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:37

-		76	((h ld or holding or support or upporting) near5 (alignm nt n ar mark)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:44
-		15	((h ld r h lding or supp rt or supporting) near5 (alignment near mark)).clm. and mask.clm. and mask.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:46
-		4	((hold or holding or support or supporting) near5 (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:48
-		1	((hold or holding or support or supporting) near5 (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:48
-		1	((hold or holding or support or supporting) near10 (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:49
-		4	((hold or holding or support or supporting) and (alignment near mark)).clm. and mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:49
-		1	mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:50
-		1	mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:50
-		10	mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:50

BEST AVAILABLE COPY

-	10	mask.clm. and mask.ab. and (first adj alignm nt adj mark).clm. and (sec nd adj alignment adj mark).clm. and ((l ctron or (charge near particl)) near beam) and (mask sam patt rn am (alignment adj mark))	USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:51
-	6	mask.clm. and mask.ab. and (first adj alignment adj mark).clm. and (second adj alignment adj mark).clm. and ((electron or (charge near particle)) near beam) and (mask same pattern same (alignment adj mark)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 10:51